

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : Franz Laermer et al.
Serial No. : To Be Assigned
Filed : Herewith
For : DEVICE AND METHOD FOR ANISOTROPIC PLASMA
ETCHING OF A SUBSTRATE,
A SILICON BODY IN PARTICULAR

Examiner : To Be Assigned
Art Unit : To Be Assigned
Docket No. : 10191/3935
Customer No. : 26646

Mail Stop PCT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT AND
37 C.F.R. § 1.125 SUBSTITUTE SPECIFICATION STATEMENT

SIR:

Please amend without prejudice the above-identified application before examination,
as set forth below.

Amendments to the Title begin at page 2 of this paper.

Amendments to the Specification begin at page 3 of this paper.

Amendments to the Claims are reflected in the listing of the claims which begin at page 4
of this paper.

Remarks begin at page 8 of this paper.

Att. Docket No. 10191/3935

Amendments to the Title:

Please replace the title with the following title:

--DEVICE AND METHOD FOR ANISOTROPIC PLASMA ETCHING OF A
SUBSTRATE, A SILICON BODY IN PARTICULAR--.

Att. Docket No. 10191/3935

Amendments to the Specification:

In accordance with 37 C.F.R. § 1.121, a Substitute Specification (including the Abstract, but without claims) accompanies this response. It is respectfully requested that the Substitute Specification (including Abstract) be entered to replace the Specification of record.